Atty.'s Docket No. 2085-00600 (IME-P002US)

Applicants: Cher Huan TAN et al.

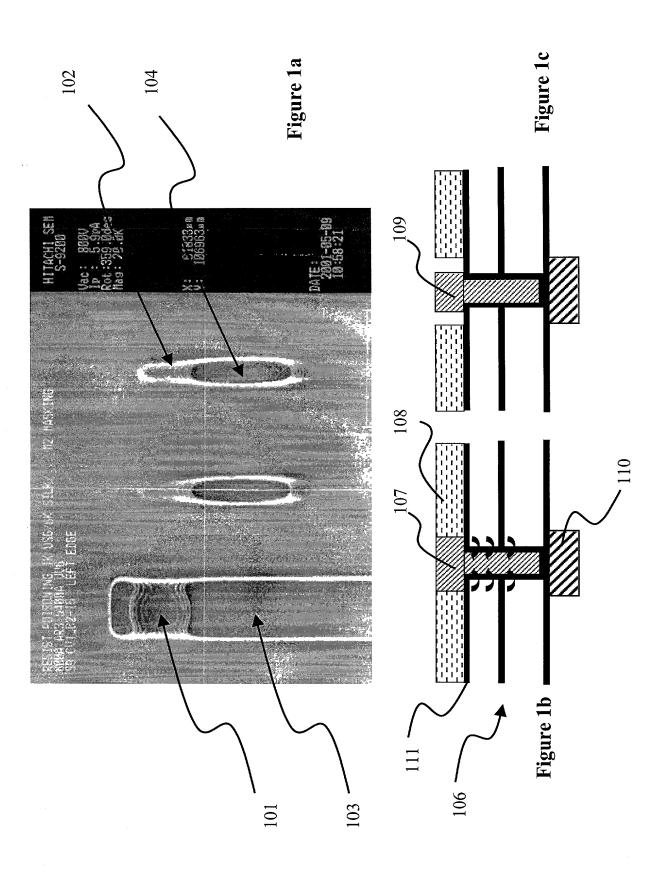
Title: Method For Preventing Photoresist Poisoning In

Semiconductor Fabrication

Sheet 1 of 4

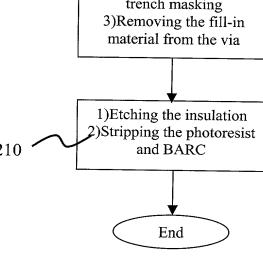
Express Mail Label No. EL889676264US

1/4



Har and Har and and and the first th

Atty.'s Docket No. 2085-00600 (IME-P002US) Applicants: Cher Huan TAN et al. Title: Method For Preventing Photoresist Poisoning In Semiconductor Fabrication Sheet 2 of 4 Express Mail Label No. EL889676264US 2/4 Start 1)Layers deposition 2)Photolithographic exposure and development 202 of 1st photoresist layer for via masking 1)Etching the insulation 2)Stripping photoresist 204 and BARC 1)Filling via with BARC or other fill-in material, or 206 wall of via lined with conformal BARC 2)Deposit BARC 1)Depositing photoresist 208 on BARC (and via lined with conformal BARC) 2)Photolithographic exposure and development of 2nd photoresist layer for trench masking 3)Removing the fill-in material from the via Figure 2 1)Etching the insulation 2)Stripping the photoresist 210 and BARC



Atty.'s Docket No. 2085-00600 (IME-P002US)

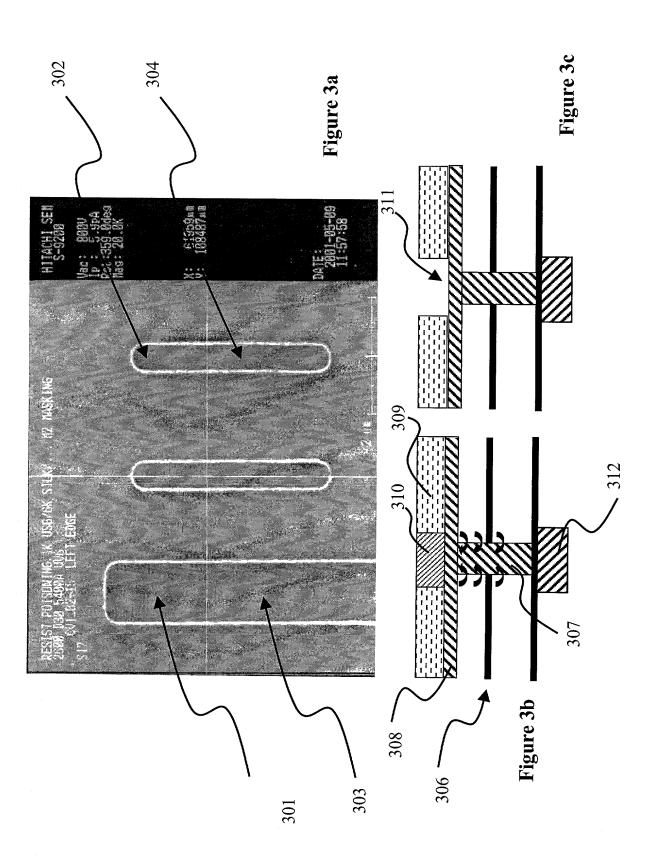
Applicants: Cher Huan TAN et al.

Title: Method For Preventing Photoresist Poisoning In Semiconductor Fabrication

Sheet 3 of 4

Express Mail Label No. EL889676264US

3/4



A STATE OF S Ħ Frank France Frank

Atty.'s Docket No. 2085-00600 (IME-P002US)

Applicants: Cher Huan TAN et al.

Title: Method For Preventing Photoresist Poisoning In

Semiconductor Fabrication

Sheet 4 of 4

Express Mail Label No. EL889676264US



